

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	7052	(427/508-521,553-559, 77,78,226).CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:07
2	L2	3978	(427/512,515,521,553, 556,557,559,77,78,226).CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:08
3	L3	1471	1 and (short adj wave shortwave "near"adj(infrared IR) NIR ("780" "2500" "1200")adj nm or ("78" "250" "120")adj (angstrom or .ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:17
4	L4	905	2 and (short adj wave shortwave "near"adj(infrared IR) NIR ("780" "2500" "1200")adj nm or ("78" "250" "120")adj (angstrom or .ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:14

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SMO/020,228

2

	L #	Hits	Search Text	DBs	Time Stamp
5	L5	370	3 and (electrode electrocatalytic\$5 electrocatalysis)	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB	2003/08/05 09:16
6	L6	244	4 and (electrode electrocatalytic\$5 electrocatalysis)	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB	2003/08/05 09:16
7	L7	14258	(electrode electrocatalytic\$5 electrocatalysis) same (short adj wave shortwave "near"adj(infrared IR) NIR ("780" "2500" "1200")adj nm or ("78" "250" "120")adj (angstrom or ".ang."))	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB	2003/08/05 09:18
8	L8	92	5 and 7	USPAT; US-P GPUB; EPO; JPO; DERWENT; IBM-TDB	2003/08/05 09:18

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	L #	Hits	Search Text	DBs	Time Stamp
9	L10	28	8 not 9	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:19
10	L9	64	6 and 7	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:21
11	L11	81	nearinfrared nearIR	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:29
12	L12	226	1 and (short adj wave shortwave nearinfrared nearIR ("near" adj(infrared IR)) NIR ("780" "2500" "1200")adj nm or ("78" "250" "120")adj (angstrom or ".ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:36

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	L #	Hits	Search Text	DBs	Time Stamp
13	L13	226	1 and (short adj wave shortwave nearinfrared nearIR! ("near!" adj(infrared IR)) NIR ("780" "2500" "1200")adj nm or ("78" "250" "120")adj (angstrom or ".ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:37
14	L14	226	1 and (short adj wave shortwave nearinfrared nearIR! ("near!" adj(infrared IR)) NIR ("780!" "2500!" "1200!")adj nm or ("78!" "250!" "120!")adj (angstrom or ".ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:39
15	L15	226	1 and (short adj wave shortwave nearinfrared nearIR! ("near"! adj(infrared IR)) NIR ("780"! "2500"! "1200"!)adj nm or ("78"! "250"! "120"!)adj (angstrom or ".ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:43
16	L16	128	2 and (short adj wave shortwave nearinfrared nearIR! ("near"! adj(infrared IR)) NIR ("780"! "2500"! "1200"!)adj nm or ("78"! "250"! "120"!)adj (angstrom or ".ang."))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:41

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	L #	Hits	Search Text	DBs	Time Stamp
17	L17	39	15 and (electrode electrocatalytic\$5 electrocatalysis)	USPAT; US-P GPUB; EPO; JPO; DERW ENT; IBM TDB	2003/08/05 09:42
18	L18	23	16 and (electrode electrocatalytic\$5 electrocatalysis)	USPAT; US-P GPUB; EPO; JPO; DERW ENT; IBM TDB	2003/08/05 09:42
19	L19	17	17 and 7	USPAT; US-P GPUB; EPO; JPO; DERW ENT; IBM TDB	2003/08/05 09:42
20	L20	1515	(electrode electrocatalytic\$5 electrocatalysis) same (short adj wave shortwave nearinfrared nearIR! ("near"! adj(infrared IR)) NIR ("780"! "2500"! "1200"!) adj nm or ("78"! "250"! "120"!) adj (angstrom or ".ang."))	USPAT; US-P GPUB; EPO; JPO; DERW ENT; IBM TDB	2003/08/05 09:44

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	L #	Hits	Search Text	DBs	Time Stamp
21	L21	15	17 and 20	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:44
22	L22	11	18 and 20	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:45
23	L23	4	21 not 22	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/08/0 5 09:45

L24 ② JPod "60243280" ✓ L16

L25 ① 427/542, CCLS, ad (short---,"ang")

L26 ① 25 ad 20 — from L23

L27 ④ 25 ad (checkbox ---)

L28 ③ 27 not(26, 22, 23)

L29 ④ 17 not(22, 23, 26, 27)

L77

this case →

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	Document ID	Issue Date	Title	Current OR	Inventor
1	US 2002011 4964 A1	20020822	Electro de treatment	428/472	Shimamune, Takayuki et al.
2	US RE37896 E	20021029	Solution for fabrication of electron-emitting devices, manufacture method of electron-emitting devices, and manufacture method of image-forming apparatus	427/126 .1	Tomida, Yoshinori et al.
3	US RE37875 E	20021015	Solid imaging process using component homogenization	264/401	Lawton, John A.
4	US 6000982 A	19991214	Method of manufacturing a cold-cathode for a discharge device	445/51	Nakamura, Osamu et al.

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	Document ID	Issue Date	Title	Current OR	Inventor
5	US 5749763 A	19980512	Display device with electro n-emitt ing device with electro n-emitt ing region insulte d from electro des	445/51	Yoshioka, Seishir o et al.
6	US 5714391 A	19980203	Method of manufac turing a compoun d semicon ductor thin film for a photoel ectric or solar cell device	438/99	Omura, Kuniyos hi et al.
7	US 5116643 A	19920526	Method for prepari ng PLZT, PZT and PLT sol-gel s and fabrica ting ferroel ectric thin films	427/126 .3	Miller, William D. et al.

	Document ID	Issue Date	Title	Current OR	Inventor
(B28) 8	In-pat ITO US 5034246 A	19910723	Method for forming tungsten oxide films	427/126 .3	Mance, Andrew M. et al.
(D56) UV-vis spent 9	US 5028455 A	19910702	Method for preparing plzt, pzt and plt sol-gel s and fabricating ferroelectric thin films	427/126 .3	Miller, William D. et al.
10	US 4946710 A	19900807	Method for preparing PLZT, PZT and PLT sol-gel s and fabricating ferroelectric thin films	427/126 .3	Miller, William D. et al.
(B6) In the market 11	US 4160185 A	19790703	Red sensitive photocathode having an aluminum oxide barrier layer	313/542	Tomasetti, Charles M. et al.
(D10) A photomulher					

(23)

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	Document ID	Issue Date	Title	Current OR	Inventor
1	(D10) [0054] Semi-conduc. layer to heat paste (baked) and w/ NER (810nm)	US 2001000 6722 A1 2001070 5	Substrate having repaired metallic pattern and method and device for repairing metallic pattern on substrate	428/209	Sakai, Osamu et al.
2	(B20) Additional seeding -- aqu. susbtm glass, expto shortnm (250 500nm)	US 6025038 A 2000021 5	Method for depositing rare-earth boride onto a substrate	427/554	Dowben, Peter A. et al.
3	Ab - UV flash lamp US 3930064 A 1975123 0	Method for curing a coating on a base	427/492	Sander, Conrad	
4	(D12) Short wave exposure 157nm	JP 6024327 9 A 1985120 3	FORMATION OF TRANSPARENT ELECTRODE		TANAKA, TAKAO et al.